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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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IN RE APPLICATION OF: Hideaki FUKUZAWA, et al.
SERIAL NO: 09/944,075
FILED: September 4, 2001
FOR: MAGNETORESISTANCE EFFECT ELEMENT

GAU: 2652
EXAMINER:

INFORMATION DISCLOSURE/RELATED CASE STATEMENT UNDER 37 CFR 1.97

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Applicant(s) wish to disclose the following information.

REFERENCES

- The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references are attached, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.
- A check is attached in the amount required under 37 CFR §1.17(p).

RELATED CASES

- Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s) is attached along with PTO 1449.
- A check is attached in the amount required under 37 CFR §1.17(p).

CERTIFICATION

- Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

DEPOSIT ACCOUNT

- Please charge any additional fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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DOCKET NO: 213589US2RD

Sheet 1 of 1

SERIAL NO: 09/944,075

Group Art Unit: 2652



STATEMENT OF RELEVANCY

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Reference AW on Form 1449:

TaO capping layer was used for specular scattering layer on tree layer.

Reference AX on Form 1449:

The concept of Nano Oxide layer (NOL) specular spin-value film was shown in this article. NOL is inserted in pinned layer for specular scattering of electrons.



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LIST OF RELATED CASES

<u>ocket Number</u>	<u>Serial or Patent No.</u>	<u>Filing or Issue Date</u>	<u>Status or Patentee</u>
PER CLIENT	09/472,144	12/27/99	UNKNOWN
PER CLIENT	6,303,218	10/16/01	KAMIGUCHI et al.
213589US2 RD*	09/944,075	09/04/01	PENDING

↑
This application

*Present application; listed for information

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